IN THE CLAIMS

- 1. (currently amended): A semiconductor light emitting device, comprising:
- a semiconductor layered portion having a light emitting layer forming portion;
- a conductive substrate; and
- a metal layer for adhering said semiconductor layered portion to said conductive substrate,

wherein said metal layer includes at least a first metal layer for making ohmic contact with said semiconductor layered portion, a second metal layer essentially consisted of Ag, and a third metal layer made of a metal which allows to adhere to said conductive substrate and said semiconductor layered portion at a low temperature:

wherein said third metal layer comprises at least one selected from a group of In. In-Zn alloy, and Sn-Zn alloy.

- 2. (original): The semiconductor light emitting device according to claim 1, wherein said first metal layer is partially removed so as to form a missing portion.
- 3. (original): The semiconductor light emitting device according to claim 2, wherein said missing portion occupies 50% or less of a surface area of said semiconductor layered portion.
- 4. (original): The semiconductor light emitting device according to claim 2, wherein a protective film is provided in said missing portion, said protection film being a film for preventing the Ag in said second metal layer from diffusing into said semiconductor layered portion, and for transmitting light emitted in said light emitting layer forming portion.
- 5. (original): The semiconductor light emitting device according to claim 4, wherein said protective film is made of SiO₂ or Al₂O₃.
- 6. (original): The semiconductor light emitting device according to claim 1, wherein Ag is added to said first metal layer.

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- 7. (original): The semiconductor light emitting device according to claim 1, wherein said second metal layer contains at least either Zn or Au at 10 atomic % or less, and comprises Ag at 90 atomic % or greater.
- 8. (original): The semiconductor light emitting device according to claim 1, wherein said second metal layer is formed to have a thickness of from 0.1 to 0.5 mm.
 - 9. (canceled)
- 10. (original): The semiconductor light emitting device according to claim 1, wherein said conductive substrate is formed of a semiconductor substrate, and a fourth metal layer for making an ohmic contact with said semiconductor substrate is provided on a side of said metal layer, said side being contact with said semiconductor substrate.
- 11. (original): The semiconductor light emitting device according to claim 10, wherein said fourth metal layer is made of at least one selected from a group of an Au-Zn alloy, an Au-Be alloy, and an Au-Ge alloy.
 - 12. (new): A semiconductor light emitting device, comprising:
 - a semiconductor layered portion having a light emitting layer forming portion;
 - a conductive substrate; and
- a metal layer for adhering said semiconductor layered portion to said conductive substrate,

wherein said metal layer includes at least a first metal layer for making ohmic contact with said semiconductor layered portion, a second metal layer essentially consisted of Ag, and a third metal layer made of a metal which allows to adhere to said conductive substrate and said semiconductor layered portion at a low temperature;

wherein said first metal layer is partially removed so as to form a missing portion.

- 13. (new): The semiconductor light emitting device according to claim 12, wherein said missing portion occupies 50% or less of a surface area of said semiconductor layered portion.
- 14. (new): The semiconductor light emitting device according to claim 12, wherein a protective film is provided in said missing portion, said protection film being a film for preventing the Ag in said second metal layer from diffusing into said semiconductor layered portion, and for transmitting light emitted in said light emitting layer forming portion.
- 15. (new): The semiconductor light emitting device according to claim 14, wherein said protective film is made of SiO₂ or Al₂O₃.
- 16. (new): The semiconductor light emitting device according to claim 12, wherein Ag is added to said first metal layer.
- 17. (new): The semiconductor light emitting device according to claim 12, wherein said conductive substrate is formed of a semiconductor substrate, and a fourth metal layer for making an ohmic contact with said semiconductor substrate is provided on a side of said metal layer, said side being contact with said semiconductor substrate.
 - 18. (new): A semiconductor light emitting device, comprising:
 - a semiconductor layered portion having a light emitting layer forming portion;
 - a conductive substrate; and
- a metal layer for adhering said semiconductor layered portion to said conductive substrate,

wherein said metal layer includes at least a first metal layer for making ohmic contact with said semiconductor layered portion, a second metal layer essentially consisted of Ag, and a third metal layer made of a metal which allows to adhere to said conductive substrate and said semiconductor layered portion at a low temperature; and

wherein Ag is added to said first metal layer.

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- 19. (new): The semiconductor light emitting device according to claim 18, wherein said conductive substrate is formed of a semiconductor substrate, and a fourth metal layer for making an ohmic contact with said semiconductor substrate is provided on a side of said metal layer, said side being contact with said semiconductor substrate.
- 20. (new): The semiconductor light emitting device according to claim 19, wherein said fourth metal layer is made of at least one selected from a group of an Au-Zn alloy, an Au-Be alloy, and an Au-Ge alloy.